

Title (en)  
SUBSTRATES WITH IMPROVED OXIDATION RESISTANCE

Title (de)  
SUBSTRATEN MIT ERHÖHTER OXIDATIONSBESTÄNDIGKEIT

Title (fr)  
SUBSTRATS POSSEDANT UNE RESISTANCE ACCRUE A L'OXYDATION

Publication  
**EP 1019920 A4 20010228 (EN)**

Application  
**EP 98957311 A 19980930**

Priority  
• US 9820404 W 19980930  
• US 94304797 A 19971001

Abstract (en)  
[origin: WO9917307A1] An alloy article having improved oxidation resistance and biaxially textured surfaces formed by thermo-mechanical techniques has up to 60 atomic % nickel, 0.1 to 25 atomic % of an oxide former selected from Mg, Al, Ti, Cr, Ga, Ge, Zr, Hf, Y, Si, Pr, Eu, Gd, Tb, Dy, Ho, Lu, Th, Er, Tm, Be, Ce, Nd, Sm, Yb, La, and mixtures thereof, with the balance copper. The surface smoothness of the article may be improved by thermomechanical techniques without impairing its surface texture. The CTE of the article may be reduced and its mechanical strength increased by incorporation of additional materials into the article without impairing its surface texture. The alloy article is useful as a conductive substrate for superconducting composites where the substrate is coated with a superconducting oxide. Methods of producing the alloy article by melting and sheath and core techniques are also disclosed.

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Citation (search report)  
• [X] EP 0392659 A2 19901017 - GEN ATOMICS [US]  
• [X] DE 19501223 A1 19960718 - KOREA MACHINERY & METAL INST [KR]  
• [A] US 4927788 A 19900522 - NAKASHIMA KAZUTAKA [JP], et al  
• [A] PATENT ABSTRACTS OF JAPAN vol. 017, no. 309 (C - 1070) 14 June 1993 (1993-06-14)  
• [A] PATENT ABSTRACTS OF JAPAN vol. 1995, no. 01 28 February 1995 (1995-02-28)  
• See references of WO 9917307A1

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